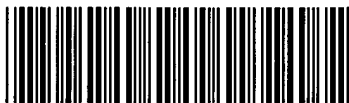


Search Notes

Application No.

10/609,476

Examiner

Stephen W. Smoot

Applicant(s)

FUJIOKA ET AL.

Art Unit

2813

SEARCHED

Class	Subclass	Date	Examiner
438	240	8/16/2004	SWS
438	253	8/16/2004	SWS
438	255	8/16/2004	SWS
438	396	8/16/2004	SWS
438	398	8/16/2004	SWS
438	591	8/16/2004	SWS
438	785	8/16/2004	SWS

S.W.S.

INTERFERENCE SEARCHED

Class	Subclass	Date	Examiner

**SEARCH NOTES
(INCLUDING SEARCH STRATEGY)**

	DATE	EXMR
Key Words: Atomic Layer Deposition - ALD, ALE; Capacitor Dielectric - Tantalum, Hafnium, Zirconium.	8/16/2004	<i>S.W.S.</i> SWS
Search Tools - EAST (attached): USPAT; US PG PUBS; Derwent; EPO; JPO; IBM TDB	8/16/2004	<i>S.W.S.</i> SWS